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TDG PATENT HARVESTING SESSION
GROUP 2—ROOM C-2

Technical Leader: Chris Lyons

TOPIC: Advanced Patterning Modules

AMD INVENTION DISCLOSURE

TLD ID# REDACTED
Sunnyvale x42110, return to MS68, Texas x55964 return to MS562

Project: ☐, Product: ☐, Process: ☐, Technology ☐, to which the invention applies (identify):

List 2 to 5 key words useful to search by to find patents or art related to this invention:

Working title of invention: Dual mask to change focus for printing small contacts
or vias

INVENTOR/SESSION PARTICIPANT ADDRESS INFORMATION IS ON THE NEXT PAGE (1A)

Inventor's signature: _____ date: _____
Inventor's printed full name: RS + all + U30.0 + Hung E. Kim Citizenship: _____
Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____
Division: _____ Directorate: _____ Dept #: _____ Dept: _____ Manager: _____
Residence address: _____
Post Office address: _____

Co-Inventor's signature: _____ date: _____
Co-Inventor's printed full name: _____ Citizenship: _____
Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____
Division: _____ Directorate: _____ Dept #: _____ Dept: _____ Manager: _____
Residence address: _____
Post Office address: _____

Co-Inventor's signature: _____ date: _____
Co-Inventor's printed full name: _____ Citizenship: _____
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Division: _____ Directorate: _____ Dept #: _____ Dept: _____ Manager: _____
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Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____
Division: _____ Directorate: _____ Dept #: _____ Dept: _____ Manager: _____
Residence address: _____
Post Office address: _____

List on additional sheet if there are more co-inventors and list total number of inventors here: _____
Name(s) of attorney(s) preferred by inventor(s) to prepare patent application, if known: _____

LAW FIRM: FOLEY & LARDNER
ATTORNEYS: PHIL ARTICOLA and TOM BILODEAU

Witness 1 initial: _____ Witness 2 initial: _____

AMD INVENTION DISCLOSURE

TLD ID# _____

Rec'd date _____

California x42110, return to MS68,

Texas x55964 return to MS562,

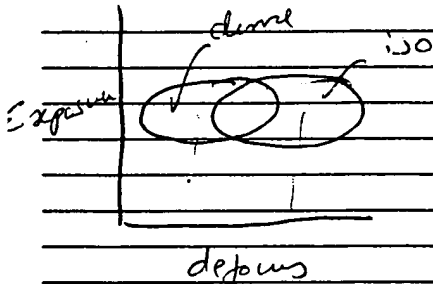
Dresden x83401 Silke Kretzschmar at MS E21-PP.

State the problem solved by this invention: _____

Brief description and/or sketch of invention (please attach copies of AMD patent notebook pages, reports or drawings): _____

As context size shrinks the experimental data shows that

The test for printing dense & isolated vias at different



→ Proposal is to use 2 masks to print the 2 types of vias separately with

2 ~~types~~ different focus settings to get best process.

- Broader claim is as we have many pitches we may use many masks with different optical settings to get best process now
↓
include illuminator, focus, NA, Sigma etc.

Patent notebook # _____ Page numbers _____ Number of drawings _____

Witness 1 initial: _____ Witness 2 initial: _____